PMMA DUV Exposure

Introduction
PMMA resist can be exposed with DUV wavelengths (200–270nm). Above wavelengths of 280nm, the polymer shows no absorption and can thus not be exposed in this wavelength range.

Coating:
PMMA resist can be spin coated on the substrate, see spin curves for film thickness versus spin speed.

Pre-Bake:
Hotplate: 180°C for 60 - 90 seconds
Convection Oven: 170°C for 30 minutes

Exposure:
Deep UV - Low sensitivity, requiring doses >500 mJ/cm² at 248nm

Developing:
60 s in MIBK : IPA (1:3)

Stopping:
30 s IPA rinse